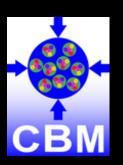


2016, Darmstadt

"Vacuum-Compatible, Ultra-Low Material Budget MVD for the CBM Experiment: Group Report"

GOETHE UNIVERSITÄT



Michal Koziel
On behalf of CBM-MVD group.
koziel@physik.uni-frankfurt.de





CBM-MVD related contributions



M. Koziel: "Vacuum-Compatible, Ultra-Low Material Budget MVD for the CBM Experiment."

Monday 14:00 HK 7.1

- M. Deveaux: "On drift fields in CMOS Monolithic Active Pixel Sensors."
 Monday 14:45 HK 7.3
- Erik Krebs: "Background rejection in dilepton analysis with CBM-MVD"
 Monday 17:45 HK 10.5
- D. Doering / M.Deveaux: "Ein Röntgenspektrometer auf der Basis von hochspannungstauglichen CMOS-Sensoren mit hochdotiertem Dopiniggradienten im aktiven Medium."

Tuesday 14:30 HK 21.2

- B. Linnik: "Status of the radiation hardness of CMOS Monolithic Active Pixels Sensors for the CBM experiment."
 Tuesday 14:45 HK 21.3
- T. Bus: "Strahlenschäden in dotiertem Silizium aufgrund Neutroneneinfangs Bor als Erweiterung des NIEL-Modells."
 Wednesday 18:30 HK 45.49
- P. Klaus: "Thin and Reliable Connectivity for the CBM-MVD"
 Thursday 18:00 HK 60.7

Outline

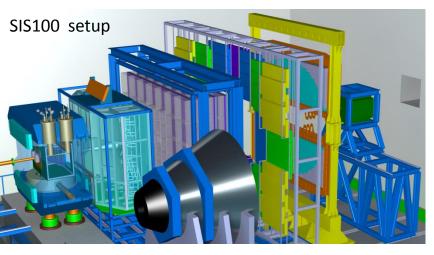
The CBM-MVD: reminder

- Simulations
 - Tracking performance
 - Background rejection in dielectron analysis

- Sensor development
- PRESTO Project

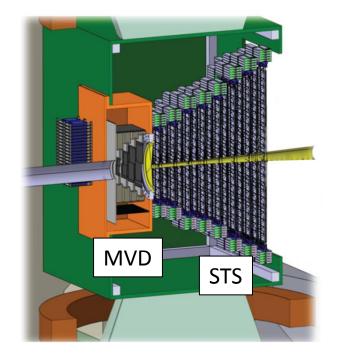
Summary

The CBM Micro Vertex Detector: Reminder p.1



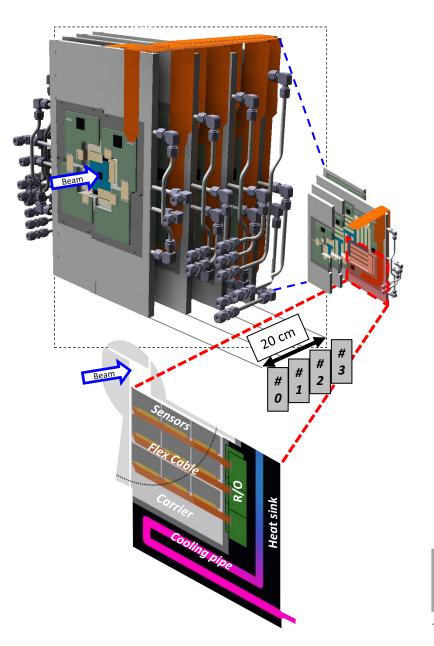
CBM-MVD:

- Improve secondary vertex resolution (open charm)
- Tracking of low-momentum particles
- Background rejection in di-electron measurements
- Hosts highly granular silicon pixel sensors featuring low material budget, fast read-out, excellent spatial resolution and robustness to radiation environment.

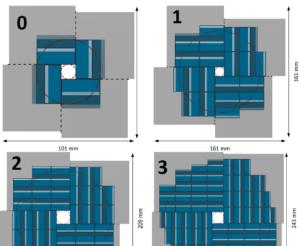


Required performances (SIS-100)					
Radiation tolerance	> 10 ¹³ n _{eq} /cm ² & >1 Mrad				
Read-out speed	> 30 kframes/s				
Intrinsic resolution	5-10 μm - physics case driven				
Operation in vacuum & magnetic field					
Support & cooling	Material budget ~ 0.3 % x/X ₀ Double-sided sensor integration				

The CBM Micro Vertex Detector: Reminder p.2

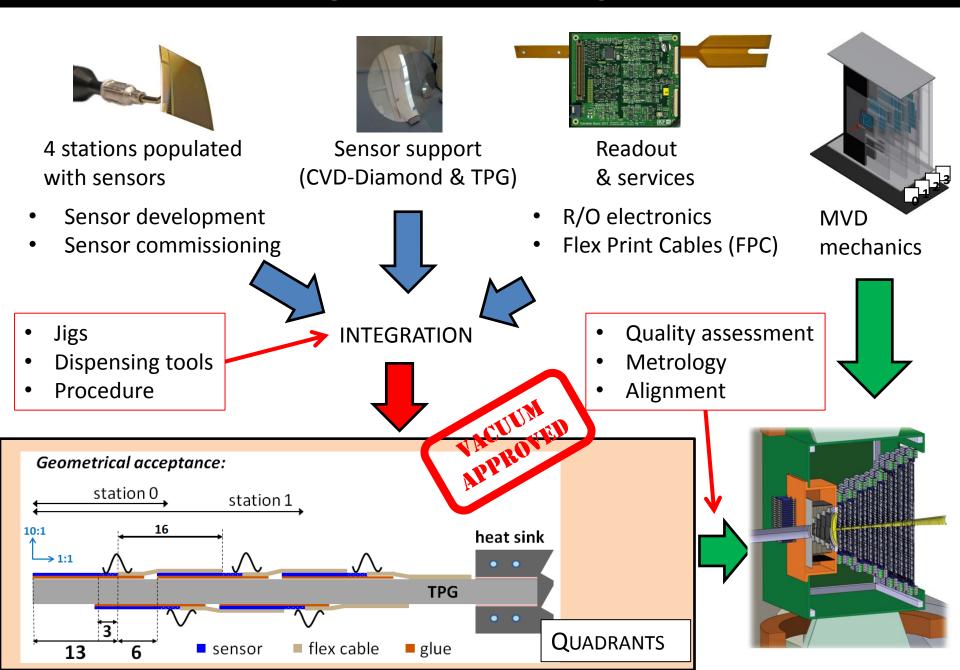


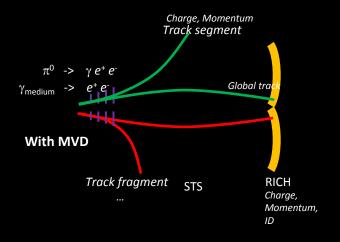
Station		Radius [mm]		Details	
No.	Distance from target [mm]	Inner	Outer	Min. # of 3x1 cm sensors	Carrier material
0	50	5.5	25	8	CVD diamond
1	100	5.5	50	36	CVD diamond
2	150	8.3	75	78	TPG
3	200	11	100	128	TPG



Minimum geometrical acceptance shown

CBM-MVD: integration challenge





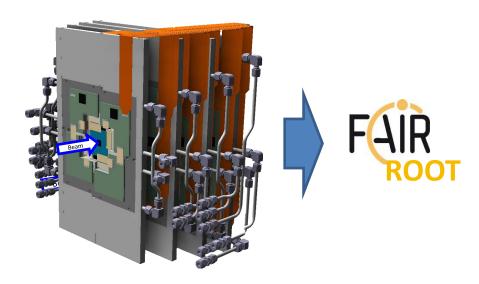
SIMULATIONS

Performance & Physics Case Studies

Erik Krebs: "Background rejection in dilepton analysis with CBM-MVD"

Monday 17:45 HK 10.5

MC simulations => MVD+STS tracking capability



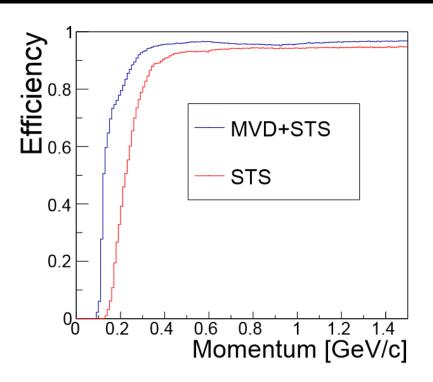


Setup = 4 MVD + 8 STS stations

Primary tracks considered

Studied:

- Impact parameter resolution
- Momentum resolution
- Tracking efficiency
- For particles with momentum smaller than 0.5 GeV/c

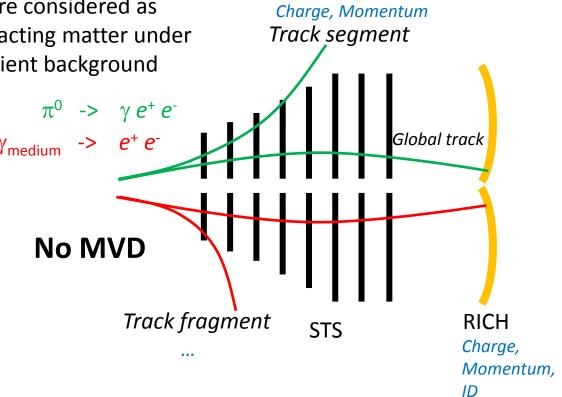


Conclusion: MVD improves the CBM tracking capability due to added value, that is spatial resolution and geometrical acceptance.

Background rejection with MVD

The light vector mesons ρ , ω and ϕ are considered as excellent probes of the strongly interacting matter under extreme conditions... but rare -> efficient background rejection.

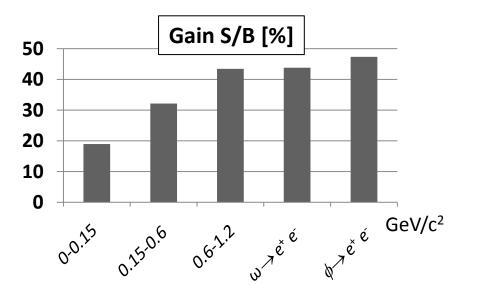
Single electron or positron tracks from incompletely detected γ -conversions and Dalitz decays of π^0 -mesons are the most abundant source contributing to the combinatorial background.

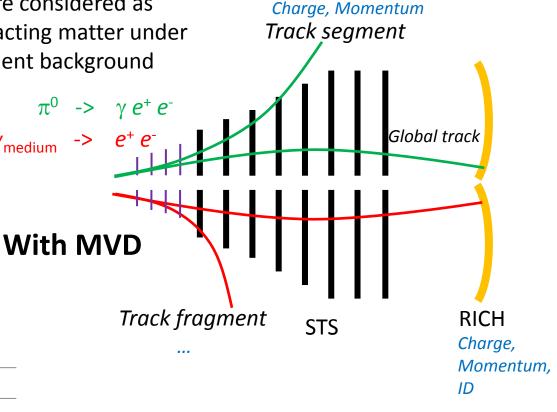


Background rejection with MVD

The light vector mesons ρ , ω and ϕ are considered as excellent probes of the strongly interacting matter under extreme conditions... but rare -> efficient background rejection.

Single electron or positron tracks from incompletely detected γ -conversions and Dalitz decays of π^0 -mesons are the most abundant source contributing to the combinatorial background.





Tracking of low momentum tracks, helps to suppress background (mainly from conversion) as being e.g. well established by HADES collaboration.



SENSOR DEVELOPMENT

- M. Deveaux: "On drift fields in CMOS Monolithic Active Pixel Sensors."
 Monday 14:45 HK 7.3
- D. Doering / M.Deveaux: "Ein Röntgenspektrometer auf der Basis von hochspannungstauglichen CMOS-Sensoren mit hochdotiertem Dopiniggradienten im aktiven Medium."

Tuesday 14:30 HK 21.2

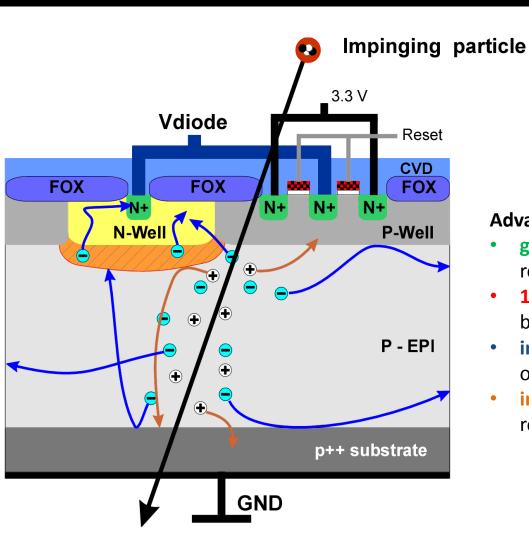
• B. Linnik: "Status of the radiation hardness of CMOS Monolithic Active Pixels Sensors for the CBM experiment."

Tuesday 14:45 HK 21.3

• T. Bus: "Strahlenschäden in dotiertem Silizium aufgrund Neutroneneinfangs Bor als Erweiterung des NIEL-Modells."

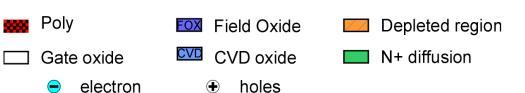
Wednesday 18:30 HK 45.49

CMOS Pixel Sensors (CPS)



Advantages of CMOS sensors:

- granularity: pixels of 10×10 μm, high spatial resolution
- 10-20 μm thick sensing volume: low material budget (typically 50 μm Si)
- **in-chip signal processing:** compact sensors with on-board intelligence, e.g. data sparsification
- in addition: cost, multi-project run frequency, room temperature operation, potentially HR EPI



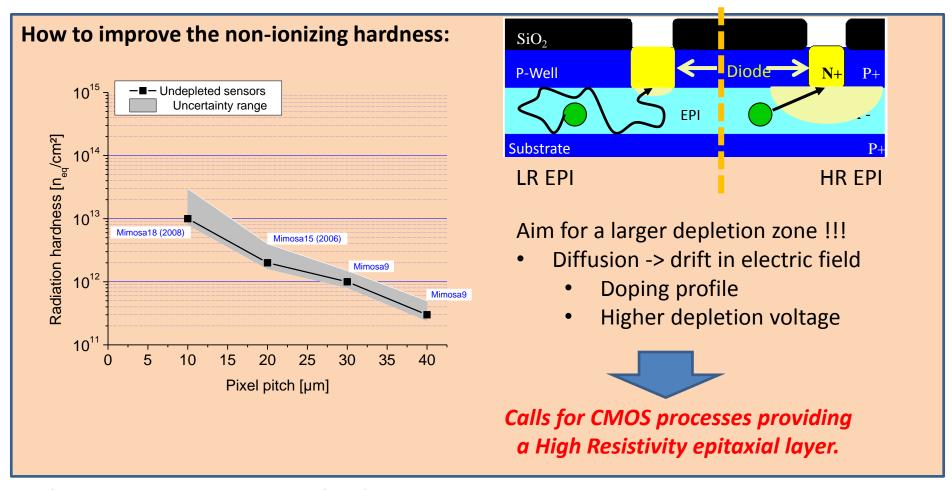
CBM-MVD sensor specification



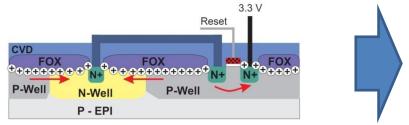
PARAMETER	Baseline
Spatial resolution	~ 5 μm
Maximum power dissipation	
(full occupancy) [mW/cm²]	< 200
Reduced rate, Station 2-3	< 350
→ Full rate, Station 0-1	
Pixel pitch	~30 x 30
	μm²
Operation temperature [°C]	-40 to +30
Operation temperature	5
gradient on sensor [K/cm]	
Radiation doses $[n_{eq}/cm^2]$	
@ -20°C	3×10^{13}
@+30°C	1×10^{13}
Radiation doses [Mrad]	
@ -20°C	3 Mrad
@+30°C	1 Mrad
Radiation doses [HI/cm ²]	10 ¹⁰ ?
	High
	uncertainty
Radiation dose (gradient)	100%
Readout time (μs)	~10
Average hit rate (1/mm²/s)	1.5×10^{5}
Peak hit rate (1/mm²/s)	7×10^{6}
Maximum Data rate (Gbps/cm²)	~1.6
Minimum Data rate (Gbps/cm²)	0.16
Encoding	24bit/hit

ARY !!!						
P	RELIMINARY!					
line	PARAMETER	Baseline				
μm 200	Efficiency → New → End of lifetime	> 99% ~99%				
350	Fake hit rate → New	10-5				
x 30 m²	→ End of lifetime Data interface	10 ⁻⁴ 320 Mbps				
o +30 5	Minimum number of data lines/sensor					
	I/O Standard	GBT-comp.				
	Bonding technology	Wedge				
$10^{13} \ 10^{13}$	Bias voltage mismatch tolerance	0.3V				
	Variation in currents	5%				
1rad	Slow control					
1rad	Clock down	Factor 2				
¹⁰ ?		(Uncertain)				
gh	Sensor surface (sensitive)	3 x 1 cm ²				
tainty	Sensor surface (insensitive)	3 x 0.3 cm ²				
0%	Thickness	50 μm				
10	ESD - Protection					
10^5	Pads for probe testing					
10 ⁶	Unique ID for sensors					
1.6	Alignment markers					
16	Temperature sensor	13				
t/hit		13				

How to improve radiation tolerance of CPS



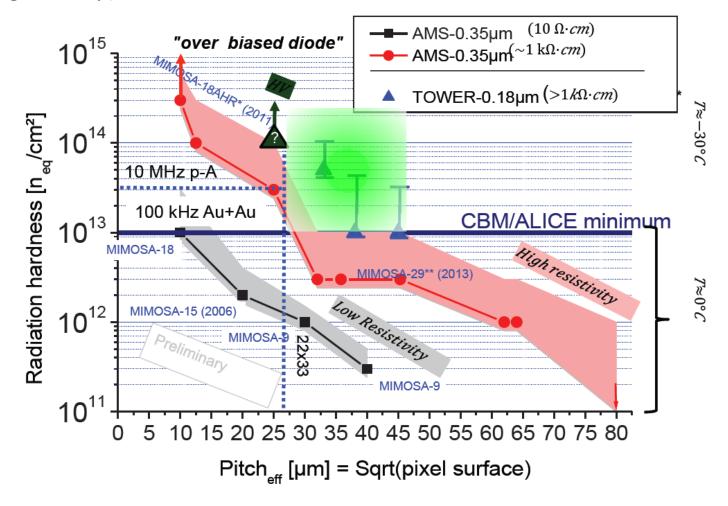
The way to improve ionizing hardness:



Investigate processes with small feature size, 0.18 µm and below.

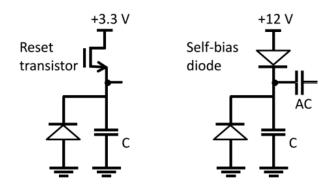
Radiation hardness: 2015 achievements

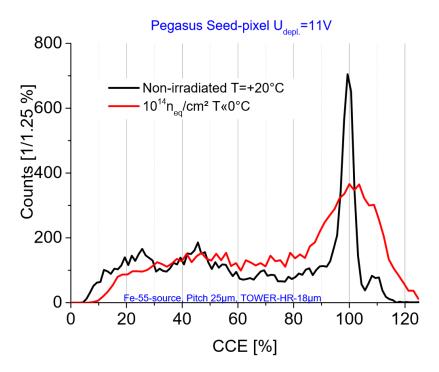
Aim: investigate the radiation hardness of the JAZZ-TOWER 0.18 μ m CMOS process **Key point:** a high-resistivity (> 1k Ω *cm) EPI (HR-EPI) layers with different doping profiles **Outcome:** top radiation tolerance for HR-EPI featuring gradient doping profile (publication during write-up)



Radiation hardness: 2015 achievements

Towards fully-depleted CMOS pixel sensors: PEGASUS sensor





Aim: Design, manufacture and study the sensor with pixels powered from higher (~12.5 V) than standard (0.6-2.8 V) bias voltage.

Outcome: High bias voltage increases the size of the depleted volume to almost (?) full epitaxial layer thickness.

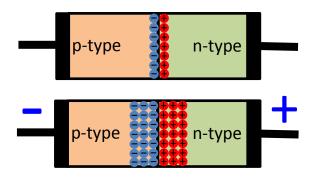


D.Doering et al., "CMOS-sensors for energy-resolved X-ray imaging"

http://dx.doi.org/10.1088/1748-0221/11/01/C01013

Why we do not deplete CMOS Pixel Sensors?





$$d = \sqrt{\frac{2\varepsilon\varepsilon_0}{e} + \left(\frac{1}{N_A} + \frac{1}{N_D}\right)(U_{bi} - U)} \sim \sqrt{U_{depl}}$$

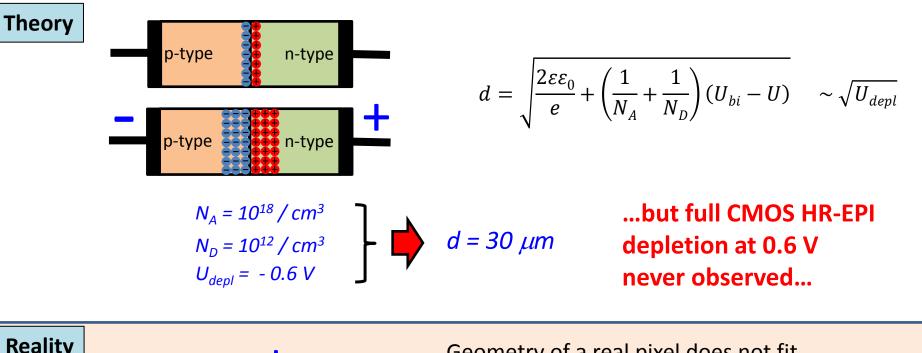
$$N_A = 10^{18} / cm^3$$

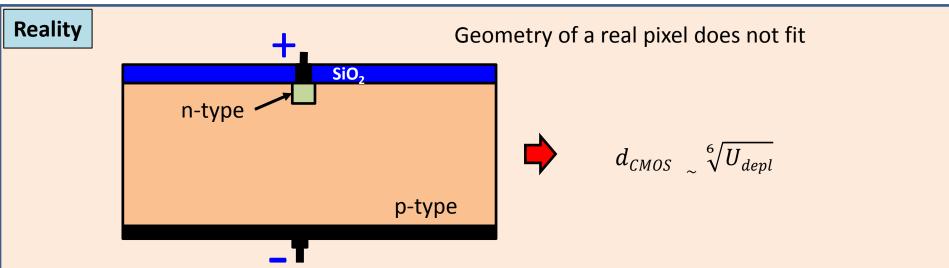
 $N_D = 10^{12} / cm^3$
 $U_{depl} = -0.6 \text{ V}$

$$d = 30 \mu m$$

...but full CMOS HR-EPI depletion at 0.6 V never observed...

Why we do not deplete CMOS Pixel Sensors?

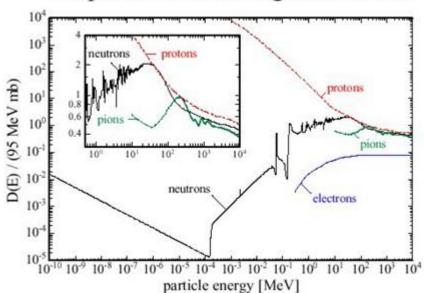




M. Deveaux: "On drift fields in CMOS Monolithic Active Pixel Sensors."

Monday 14:45 HK 7.3

Displacement damage functions



According to NIEL (non-ionizing energy loss) scaling, any particle fluence can be reduced to an equivalent 1 MeV neutron fluence producing the same bulk damage in a specific semiconductor. The scaling is based on the hypothesis that generation of bulk damage is due to non-ionizing energy transfers to the lattice.

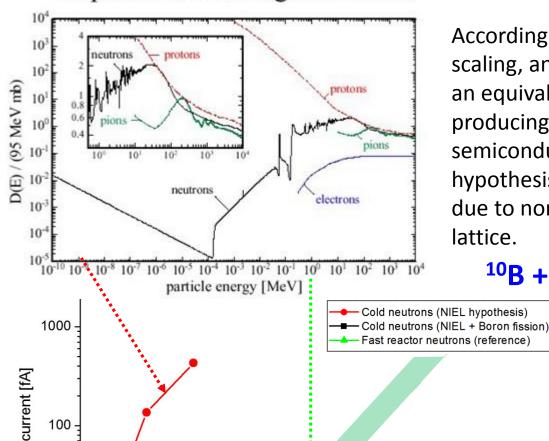
$$^{10}B + n => Li + \alpha + 3MeV$$



Radiation from this process to be considered

No problem if P-doping << 10¹⁵cm³

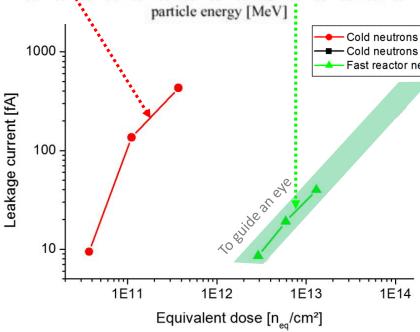
Displacement damage functions



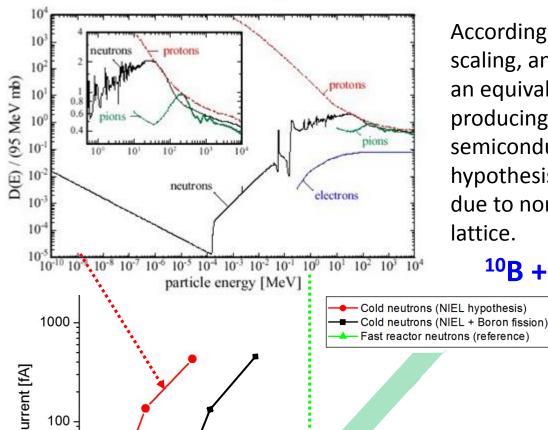
According to NIEL (non-ionizing energy loss) scaling, any particle fluence can be reduced to an equivalent 1 MeV neutron fluence producing the same bulk damage in a specific semiconductor. The scaling is based on the hypothesis that generation of bulk damage is due to non-ionizing energy transfers to the lattice.

 $^{10}B + n => Li + \alpha + 3MeV$





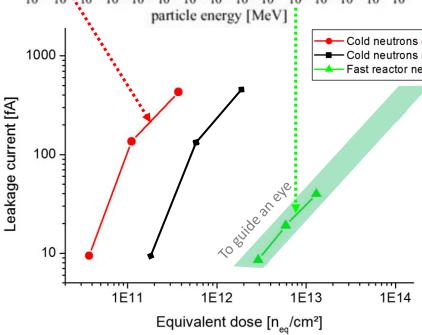
Displacement damage functions



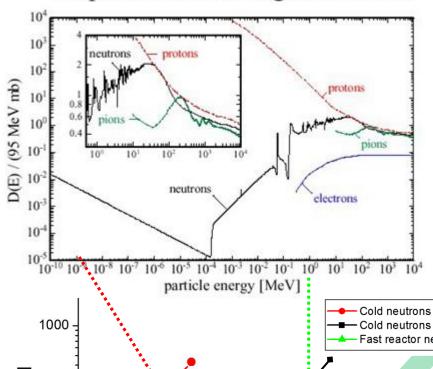
According to NIEL (non-ionizing energy loss) scaling, any particle fluence can be reduced to an equivalent 1 MeV neutron fluence producing the same bulk damage in a specific semiconductor. The scaling is based on the hypothesis that generation of bulk damage is due to non-ionizing energy transfers to the lattice.

$$^{10}B + n => Li + \alpha + 3MeV$$





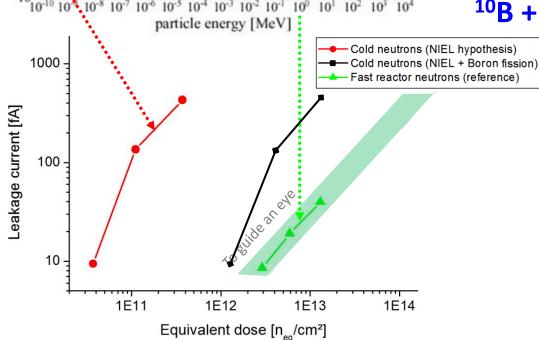
Displacement damage functions



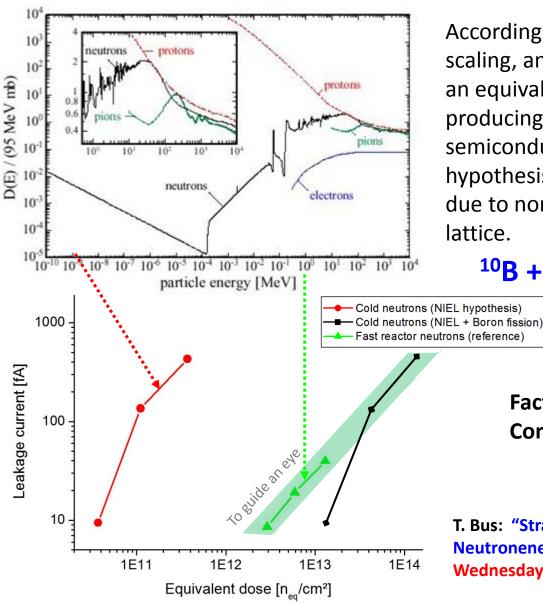
According to NIEL (non-ionizing energy loss) scaling, any particle fluence can be reduced to an equivalent 1 MeV neutron fluence producing the same bulk damage in a specific semiconductor. The scaling is based on the hypothesis that generation of bulk damage is due to non-ionizing energy transfers to the lattice.

$$^{10}B + n => Li + \alpha + 3MeV$$





Displacement damage functions



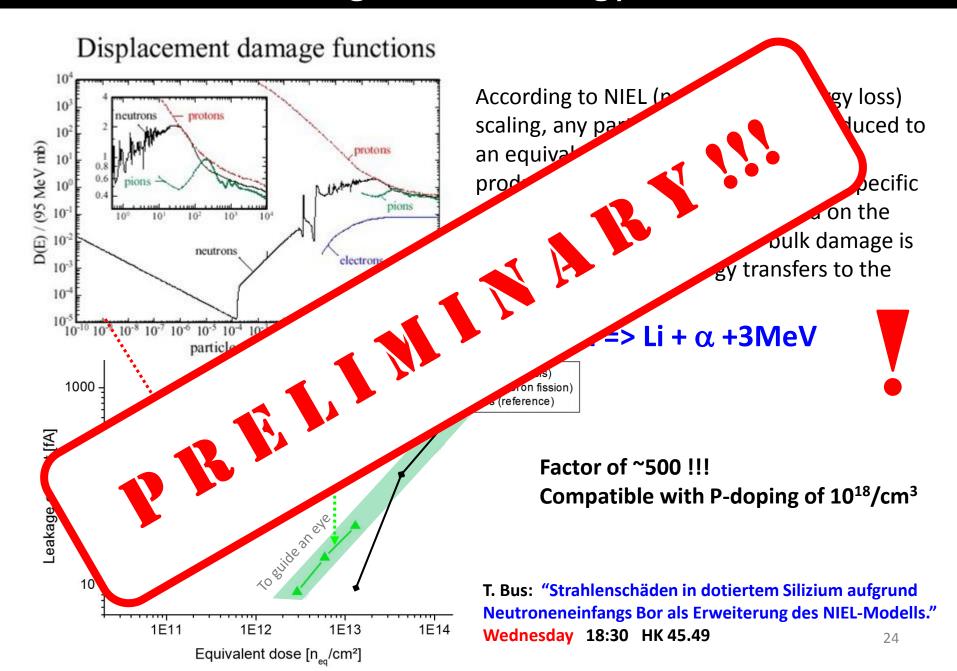
According to NIEL (non-ionizing energy loss) scaling, any particle fluence can be reduced to an equivalent 1 MeV neutron fluence producing the same bulk damage in a specific semiconductor. The scaling is based on the hypothesis that generation of bulk damage is due to non-ionizing energy transfers to the lattice.

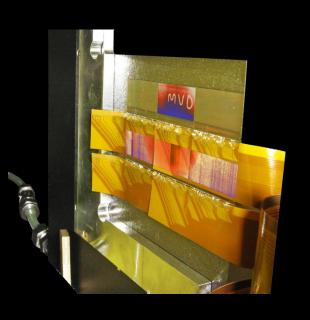
 $^{10}B + n => Li + \alpha + 3MeV$

Factor of ~500 !!!

Compatible with P-doping of 10¹⁸/cm³

T. Bus: "Strahlenschäden in dotiertem Silizium aufgrund Neutroneneinfangs Bor als Erweiterung des NIEL-Modells." Wednesday 18:30 HK 45.49





PRESTO Project



P. Klaus, M.Wiebusch et al., "Prototyping the read-out chain of the CBM Micro Vertex Detector"

Accepted for publication

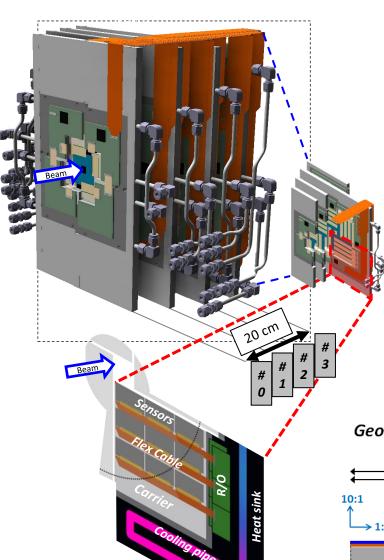


M.Koziel et al., "Vacuum-Compatible, Ultra-Low Material Budget Micro Vertex Detector of the Compressed Baryonic Matter Experiment at FAIR" In preparation

P. Klaus: "Thin and Reliable Connectivity for the CBM-MVD"

Thursday 18:00 HK 60.7

PRESTO: PREcursor of the Second sTatiOn



WHAT'S THAT?

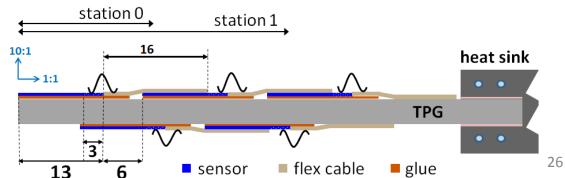
15 MIMOSA-26 sensors integrated on both sides of a 8×8 cm² 350 μ m thin TPG carrier

- 9 on the front in a 3 × 3 arrangement
- 6 sensors on the back in a 2×3 arrangement
- Support size of MVD station #1
- Complexity ~ of MVD station #2
- Sensors are connected with the DAQ system employing new flex cables (10 FPCs / PRESTO)

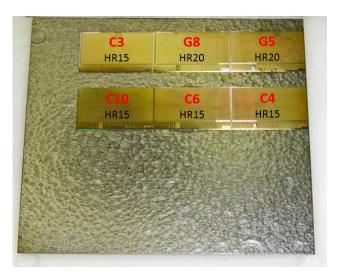
MOTIVATION:

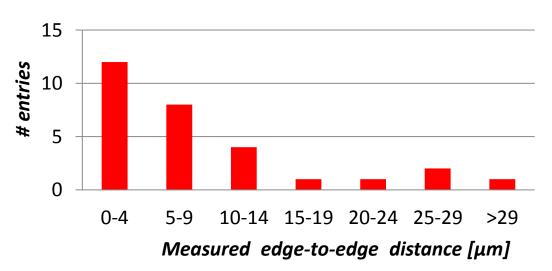
2nd phase of prototyping (1st step, station "0" oriented) aiming for 2-sided, vacuum compatible, quadrant integration.

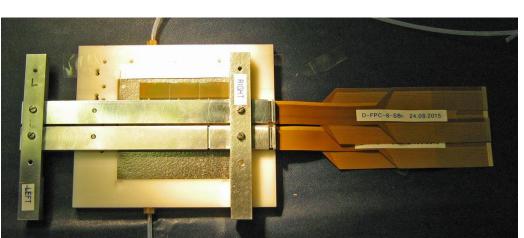
Geometrical acceptance:



PRESTO: construction

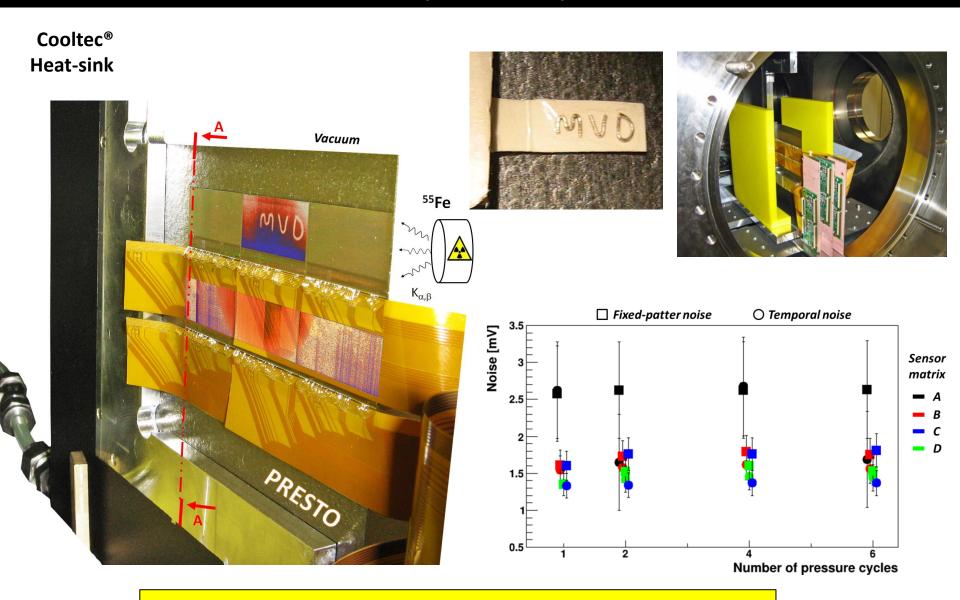








PRESTO: vacuum compatibility



No change in sensor performance after several pressure cycles (atmospheric – 10⁻⁴ mbar)

Accomplished MVD-related PhDs: 2015



Dennis Doering

"Untersuchungen zur Verbesserung der Strahlenhärte von CMOS-Sensoren zum Einsatz in Vertexdetektoren von Schwerionenexperimenten."



Tobias Tischler

"Mechanical Integration of the Micro Vertex Detector for the CBM experiment."





Borislay Milanovic

"Development of the Readout Controller for the CBM Micro Vertex Detector."

SUMMARY:

- Wide range of activities towards the CBM-MVD
- PRESTO project
 - proves that one can built a vacuum compatible device based on a bare TPG carrier and employing ultra-thin, but industrial flex cable.
 - Construction of the second side is ongoing (last R&D step before MVD production)
- MVD: flexibility to adopt to physics case
- Sensors implemented in Jazz-Tower CMOS process seems to meet radiation tolerance requirements
- Technical specification of the MVD sensor in advance stage, synergy with other experiments, mainly STAR (running!) and ALICE upgrade

Thank you for your attention...

